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- (71) 申请人: 盛美半导体设备(上海)股份有限公司(**ACM RESEARCH (SHANGHAI), INC.**) [CN/CN];
中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。
- (72) 发明人: 李泽然(**LI, Zeran**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢,

Shanghai 201203 (CN)。初振明(**CHU, Zhenming**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。仲召明(**ZHONG, Zhaoming**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。何西登(**HE, Xideng**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。

- (74) 代理人: 上海专利商标事务所有限公司(**SHANGHAI PATENT & TRADEMARK LAW OFFICE, LLC**); 中国上海市徐汇区桂平路435号, Shanghai 200233 (CN)。
- (81) 指定国(除另有指明, 要求每一种可提供的国家保护): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CV, CZ, DE, DJ, DK, DM, DO, DZ, EC, EE, EG, ES, FI,

(54) **Title:** SPLASH-PROOFING DEVICE FOR PHOTORESIST STRIPPING PROCESS, PHOTORESIST STRIPPING APPARATUS, AND CHEMICAL SOLUTION DELIVERY APPARATUS

(54) 发明名称: 一种去胶工艺中的防溅射装置、去胶设备以及输液设备

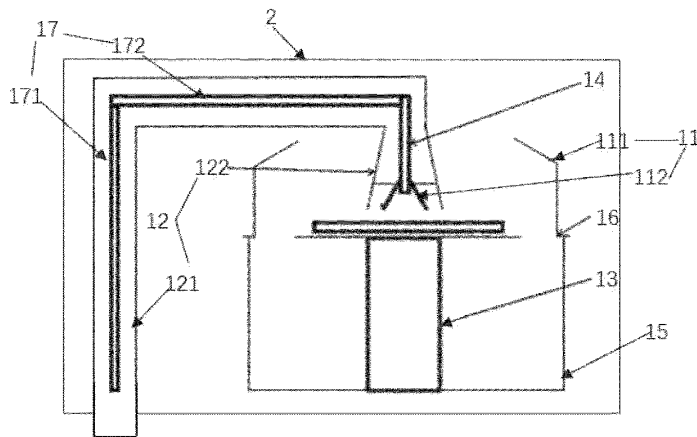


图 1

(57) **Abstract:** The present invention relates to the field of semiconductor device manufacturing, and specifically to a splash-proofing device for a photoresist stripping process, a photoresist stripping apparatus, and a chemical solution delivery apparatus. The splash-proofing device is arranged in a chamber, and specifically comprises a blocking assembly, an exhaust assembly, a bearing platform, and a nozzle. The bearing platform is configured to bear a substrate, and the nozzle is arranged above the bearing platform at a preset height. The blocking assembly comprises a protective cover, which surrounds the periphery of the substrate and is used for preventing chemical solution sprayed onto the substrate from splashing into the chamber. The exhaust assembly comprises an exhaust duct and an exhaust hood which are in communication with each other, the exhaust hood being arranged on the periphery of the nozzle,

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and an air suction port of the exhaust hood being disposed above the substrate; the exhaust assembly is configured to draw splashed chemical solution out of the chamber. The protective cover forms a protective barrier, which can effectively block the chemical solution splashing. The exhaust assembly, by means of air suction, carries the atomized chemical solution away from the exhaust hood and out of the chamber through the exhaust duct, thus further blocking the chemical solution splashing.

(57) 摘要: 本发明涉及半导体器件制造领域, 具体为一种去胶工艺中的防溅射装置、去胶设备以及输液设备。防溅射装置设于腔室内, 具体包括阻挡组件、排气组件、载物台和喷嘴; 载物台用于承载基板, 喷嘴以预设高度设置在载物台的上方; 阻挡组件包括保护罩, 保护罩围设在基板的外周用于阻挡喷涂在基板上的药液溅射至腔室内。排气组件包括互相连通的排气通管和排气罩, 排气罩设置在喷嘴的外周, 排气罩的抽风口设置在基板的上方, 排气组件用于将溅射的雾化药液吸抽至腔室外部。保护罩形成保护屏障能够高效地阻挡药液溅射。排气组件以抽气地方式将雾化药液由排气罩, 再经排气通管带出腔室, 进一步地阻挡药液飞溅。